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Fractal Analysis of Nanostructured Silver Film Surface

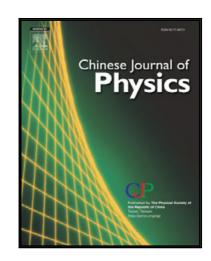
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PII: S0577-9073(17)31091-2 DOI: 10.1016/j.cjph.2017.10.015

Reference: CJPH 373

To appear in: Chinese Journal of Physics

Received date: 27 August 2017 Revised date: 23 October 2017 Accepted date: 25 October 2017



Please cite this article as: M. Nasehnejad, G. Nabiyouni, M. Gholipour Shahraki, Fractal Analysis of Nanostructured Silver Film Surface, *Chinese Journal of Physics* (2017), doi: 10.1016/j.cjph.2017.10.015

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Highlights

- In this work, electrodeposited silver thin films were characterized using X-ray diffraction and atomic force microscopy techniques.
- Calculation of standard deviation surface roughness indicated that the films grow as a power-law in time (thickness) with growth exponent of β =0.67.
- The average value of Hurst exponent is found to be 0.68 using rescaled range analyses.
- The results indicate that grain size and morphology of electrodeposited silver thin films can easily be controlled using different thickness.
- Fractal analysis revealed that the value of the fractal dimension of the samples increases as the film thickness increases.

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